



Next-Level Surface Metrology—Advances in Sensors, Data Analysis and Simulation

Guest Editors:

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Deadline for manuscript
submissions:

25 January 2025

Message from the Guest Editors

Dear Colleagues,

Advancements in surface processing lead to novel and interesting problems in the research and development of processes accompanying metrology. The aim of this Special Issue is to open discussion and technical routes for further developments in this topic across the disciplines of physicists, laser engineers, data-processing experts, and system theorists.

Please submit your manuscripts related, but not limited, to the following areas:

- Low-coherence interferometric metrology techniques (incl. OCT and others).
- Microscopy and coherent techniques (e.g., speckle interferometry).
- From lab to sensor (technologies for sensor fusion, autonomous calibration, and sensing as well as multi-domain sensing).
- Optical metrology-related data-processing approaches (AI, sparse data, fingerprint techniques, and others).
- Closed-loop system description, design, calibration, and/or evaluation (combination of metrology and surface processing tools) in the context of photonic surface processing and characterization.

